

POLISHING APPARATUS AND DRESSING METHOD

ABSTRACT OF THE DISCLOSURE

An apparatus for polishing a surface of a substrate by
slidingly engaging the surface with a polishing surface of
5 an abrasive member has a dressing member for dressing the
polishing surface of the fixed abrasive member. The
dressing member has a dressing surface provided with
projections having an angular portion of an obtuse angle of
not less than (100°).

Figure 2(A)